

REFERENCES

1. Andrews, R. and Geva, S., 2002, Rule extraction from local cluster neural nets. *Neurocomputing*, 47, 1-20.
2. Box, G. E. P. and Jenkins, G. M., 1976, *Time Series Analysis, Forecasting and Control* 2nd edn (San Francisco: Holden-Day).
3. Box, G. E. P. and Kramer, T., 1992, Statistical process monitoring and feedback adjustment-a discussion. *Technometrics*, 34, 251-285.
4. Box, G. E. P., Jenkins, G. M. and Reinsel, G., 1994 *Time Series Analysis, Forecasting and Control* 3rd edn (Englewood Cliffs, NJ: Prentice-Hall).
5. Box, G. E. P. and Luceño, A., 1997, *Statistical Control - By Monitoring and Feedback Adjustment* (New York: Wiley).
6. Breiman, L. and Spector, P., 1992, Submodel selection and evaluation in regression: the X-random case. *International Statistics Review*, 60, 291-319.
7. Brockwell, P. J. and Davis, R. A., 1996, *Introduction to Time Series and Forecasting* (New York: Springer-Verlag).
8. Butler, S. W. and Stefani, J. A., 1994, Supervisory run-to-run control of a polysilicon gate etch using in situ ellipsometry. *IEEE Transactions on Semiconductor Manufacturing*, 7, 193-201.
9. Chen, A. and Elsayed, E. A., 2002, Design and performance analysis of the exponentially weighted moving average mean estimate for processes subject to random step changes. *Technometrics*, 44, 379-389.
10. Chen, A. and Guo, R. S., 2001, Age-based double EWMA controller and its application to CMP processes. *IEEE Transactions on Semiconductor Manufacturing*, 14, 11-19.
11. Cheng, B. and Titterton, D. M., 1994, Neural networks: a review from a statistical perspective. *Statistical Science*, 9, 2-54.

12. Del Castillo, E. and Hurwitz, A., 1997, Run-to-run process control: literature review and extensions. *Journal of Quality Technology*, 29, 184-196.
13. Del Castillo, E., 1999, Long run and transient analysis of a double EWMA feedback controller. *IIE Transactions*, 31, 1157-1169.
14. Del Castillo, E., 2001, Some properties of EWMA feedback quality adjustment schemes for drifting disturbance. *Journal of Quality Technology*, 33, 153-166.
15. Del Castillo, E., 2002, Closed-loop disturbance identification and controller tuning for discrete manufacturing processes. *Technometrics*, 44, 134-141.
16. Del Castillo, E., 2002, *Statistical Process Adjustment for Quality Control* (New York:Wiley).
17. Del Castillo, E. and Rajagopal, R., 2002, A multivariate double EWMA process adjustment scheme for drifting processes. *IIE Transactions on Quality and Reliability Engineering*, 34, 1055-1068.
18. Del Castillo, E. and Yeh, J. Y., 1998, An adaptive run-to-run optimizing controller for linear and nonlinear semiconductor processes. *IEEE Transactions on Semiconductor Manufacturing*, 11, 285-295.
19. Deming, W. E., 1986, *Out of the Crisis*. Massachusetts Institute of Technology, Center for Advanced Engineering Studies, Cambridge, MA.
20. Fan, S.-K. S., Jiang, B. C., Jen, C. H. and Wang, C. C., 2002, SISO run-to-run feedback controller using triple EWMA smoothing for semiconductor manufacturing processes. *International Journal of Production Research*, 40, 3093-3120.
21. Fatin, W. F., Hahn, G. J. and Tucker, W. T., 1990, Discussion. *Technometrics*, 32, 1-29.
22. Guo, R. and Chen, J., 2002, An EWMA-based process mean estimator with dynamic tuning capability. *IIE Transactions on Quality and Reliability*

- Engineering*, 34, 573-582.
23. Hunter, J. S., 1986, The exponentially weighted moving average. *Journal of Quality Technology*, 18, 203-210.
 24. Ingolfsson, A. and Sachs, E., 1993, Stability and sensitivity of an EWMA controller. *Journal of Quality Technology*, 25, 271-287.
 25. Lucas, J. M. and Saccucci, M. S., 1992, Exponentially weighted moving average control schemes: properties and enhancements. *Technometrics*, 32, 1-29.
 26. Luceño, A., 1995, Choosing the EWMA parameter in engineering process control. *Journal of Quality Technology*, 27, 162-168.
 27. Montgomery, D. C., 1996, *Introduction to Statistical Quality Control* 3rd edn (New York:Wiley).
 28. O'Shaughnessy, P. and Haugh, L., 2002, EWMA-based bounded adjustment scheme with adaptive noise variance estimation. *Journal of Quality Technology*, 34, 327-339.
 29. Pan, R. and Del Castillo, E., 2001, Identification and fine tuning of closed-loop processes under discrete EWMA and PI adjustments. *Quality and Reliability Engineering International*, 17, 419-427.
 30. Patel, N. and Jenkins, S., 2000, Adaptive optimization of run-to-run controllers: the EWMA example. *IEEE Transactions on Semiconductor Manufacturing*, 13, 97-107.
 31. Roberts, S. W., 1959, Control chart tests based on geometric moving averages. *Technometrics*, 1, 239-250.
 32. Sachs, E., Hu, A., and Ingolfsson, A., 1995, Run by run process control: combining SPC and feedback control. *IEEE Transactions on Semiconductor Manufacturing*, 8, 26-43.
 33. Sastri, T., 1988, An adaptive estimation. *IIE Transactions*, 20, 176-185.

34. Sjoberg, J. and Agarwal, M., 2002, Trajectory tracking in batch processes using neural controllers. *Engineering Applications of Artificial Intelligence*, 15, no.1, pp.41-51.
35. Smith, T. and Boning, D., 1997, A self-tuning EWMA controller utilizing artificial neural network function approximation techniques. *IEEE Transactions on Components, Packaging, and Manufacturing Technology-Part C*, 20, 121-132.
36. Su, C.-T., Yang, T. and Ke, C.-M. 2002, A neural-network approach for semiconductor wafer post-sawing inspection, *IEEE Transactions on Semiconductor Manufacturing*, 15, no. 2, 260-266.
37. Witten, I. H. and Frank, E., 2001, *Data Mining: Practical Machine Learning Tools and Techniques with Java Implementations*, Morgan Kaufmann Publishers, San Francisco.
38. Wang, X. A. and Mahajan, R. L., 1996, Artificial neural network model-based run-to-run process controller. *IEEE Transactions on Components, Packaging, and Manufacturing Technology-Part C*, 19, 19-26.
39. Zhang, P., 1993, Model selection via multifold cross-validation. *Annals of Statistics*, 21, 299-311.